

IN THE ABSTRACT:

Please substitute the following Substitute Abstract for the originally filed Abstract.

SUBSTITUTE ABSTRACT

There are provided a dust generation preventing structure of a wafer storage case and a process for preventing dust generation thereof, wherein dust generation is effectively prevented by blocking or suppressing free movement of particles constantly generated from a surface of a wafer storage case of a synthetic resin with a coating layer of a surfactant, and a wafer storing method using the wafer storage case. The wafer storage case of synthetic resin is used for housing wafers, ~~wherein~~ and a surface of the wafer storage case is coated with a coating layer of a coating agent to prevent dust generation from the surface.